

**Examiner-Initiated Interview Summary**

Application No.

09/732,928

Applicant(s)

SHIMAZU ET AL.

Examiner

James P. Hughes

Art Unit

2881

**All Participants:**(1) James P. Hughes.(2) David Safran.**Status of Application:** Pending

(3) \_\_\_\_\_

(4) \_\_\_\_\_

**Date of Interview:** 16 September 2003**Time:** AM**Type of Interview:**☒ Telephonic☐ Video Conference☐ Personal (Copy given to: ☐ Applicant ☐ Applicant's representative)Exhibit Shown or Demonstrated: ☐ Yes ☒ No

If Yes, provide a brief description:

**Part I.**

Rejection(s) discussed:

*Potential new limitations to claims 1 and 9 to overcome new rejections based on IDS documents.*

Claims discussed:

*1 and 9*

Prior art documents discussed:

*Bohlen et al. "High Throughput Submicron Lithography with Electron Beam Proximity Printing" and Utsumi "Low Energy e-beam Proximity Projection Lithography" that were submitted in the IDS.***Part II.**

SUBSTANCE OF INTERVIEW DESCRIBING THE GENERAL NATURE OF WHAT WAS DISCUSSED:

*An added limitation of "wherein, said plurality of masks comprise at least two masks which are non-complimentary" to claims 1 and 9 was suggested by the examiner and rejected by applicant on September 22, 2003.***Part III.**

- ☐ It is not necessary for applicant to provide a separate record of the substance of the interview, since the interview directly resulted in the allowance of the application. The examiner will provide a written summary of the substance of the interview in the Notice of Allowability.
- ☒ It is not necessary for applicant to provide a separate record of the substance of the interview, since the interview did not result in resolution of all issues. A brief summary by the examiner appears in Part II above.

  
JOHN R. LEE  
SUPERVISORY PATENT EXAMINER  
TECHNOLOGY CENTER 2800

(Examiner/SPE Signature)

(Applicant/Applicant's Representative Signature – if appropriate)